

L Number	Hits	Search Text	DB	Time stamp
1	37	wafer AND ((oxygen NEAR5 concentration) NEAR15 threshold)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/10/19 13:19
-	187	(oxygen NEAR3 concentration) NEAR10 (oxide NEAR7 thickness)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/10/18 10:24
-	59	(oxygen NEAR3 concentration) NEAR10 (oxide NEAR7 thickness) AND leak\$5	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/10/18 17:13
-	11	(oxygen NEAR3 concentration) NEAR10 (wafer NEAR7 thickness) AND leak\$5	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/10/18 17:14
-	5201	wafer NEAR10 (thickness NERA10 threshold) AND leak\$5	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/10/18 17:21
-	71	wafer NEAR10 (thickness NERA10 threshold) SAME (oxygen NEAR3 concentration) AND leak\$5	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/10/18 17:22